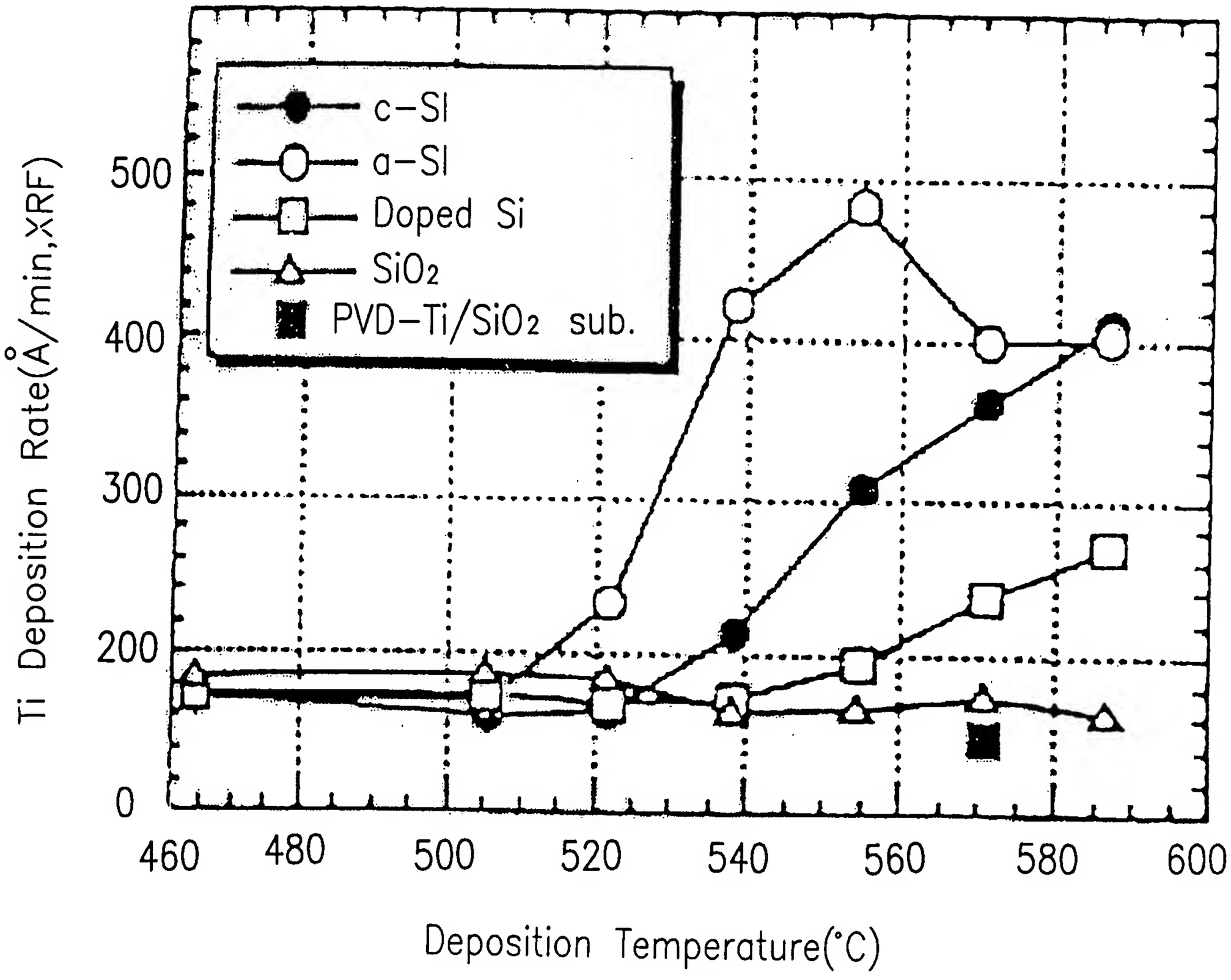
c-Si
a-Si
Doped Si
SiO2
PVD-Ti/SiO2 sub.
Ti Deposition Rate(Å/min,XRF)
500
400
300
200
0
460
480
500
520
540
560
580
600
Deposition Temperature(°C)

FIG. 5